

# Deep and Extreme Ultraviolet Lithography: Insights from the Industry's Leading Technology Provide

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The semiconductor industry is driven by affordable shrink – the ability to make smaller, more energy-efficient transistors at the right price. Reducing the size of transistors means that more can be packed into a given area, resulting in increased functionality and improved performance. Lithography is a key driver for shrink, enabling what is known as geometric scaling.

In this session we will present ASML innovations that pushed optical lithography resolution by 2 orders of magnitude within less than 40 years. In particular, we will focus on the leading-edge 0.55NA EUV technology that delivers 8nm resolution and is being introduced this year at Intel.